Form PTO 14 (Modified)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY DOCKET NO. 242859USODIV		SERIAL NO. NEW APPLICATION			
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-1	AA	<del>+</del>	06/28/94	Gelatos, et al.	<b></b> '	<b></b>	<b></b>	
<del>-</del>	AB	<del></del>	08/2002	Takaki, et al.	<b></b> '	<b></b>	<b> </b>	
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	AX	NITRIDE", Elsevier Sci	cience S. A. 199	•				
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A	AZ	FILMS DEPOSITED B'	M.Z. Karim, et al., "CHARACTERIZATION OF MIXED-PHASE BN THIN FILMS DEPOSITED BY PLASMA CVD", Surface and Coatings Technology (1993) Vol. 60, pgs. 502-505  Additional References sheet(s) attack				rences sheet(s) attached	
Examiner		7			Date Con		7/05	
*Examiner: Initial if reference is considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								

Form PTO 1449		U.S. DEPARTMENT OF COMMERCE	ATTY DOCKET NO.	SERIAL NO.			
(Modified)		PATENT AND TRADEMARK OFFICE	242859US0DIV	NEW APPLICATION			
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LIST OF	REFER	RENCES CITED BY APPLICANT	Hitoshi SAKAMOTO, et al.				
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	AAC	A.V. Gelatos, et al., Materials Research Society Symposium Proceedings, Vol. 260, pgs. 347-354, "THE PROPERTIES OF A PLASMA DEPOSITED CANDIDATE INSULATOR FOR FUTURE MULTILEVEL INTERCONNECTS TECHNOLOGY", 1992					
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Form PTO 1449 (Modified)		U.S. DEPARTIMENT AND TR	OMMERCE ROEMARK OFFICE	ATTY DOCKET NO. 242859US0DIV		SERIAL (	
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